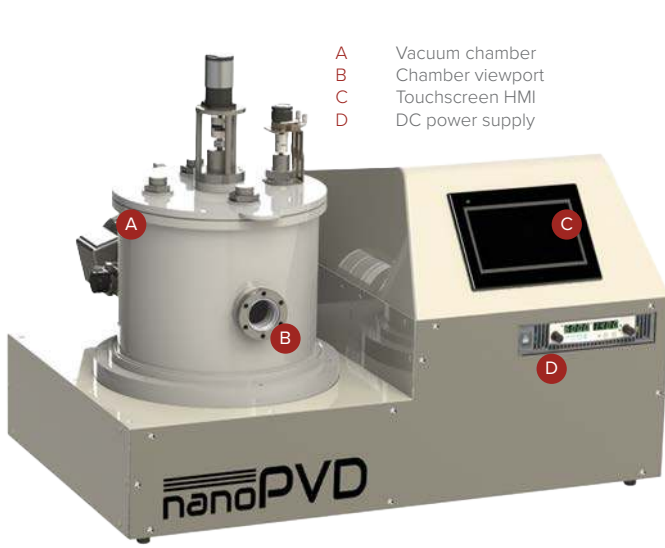


nanoPVD-S10A by Moorfield.

Research-grade magnetron sputtering.





A Vacuum chamber
B Chamber viewport
C Touchscreen HMI
D DC power supply



E Hardware connections
F Turbomolecular pump
G Electrical connections
H Water/gas/data connections

Benchtop, turnkey system for high performance RF and DC magnetron sputtering. Compact as an electron microscopy coater, but with research-grade results.

Recently introduced, nanoPVD model S10A is a magnetron sputtering system designed for repeatable coating of metals or inorganics (e.g., oxides or nitrides). Compact and suitable for benchtop location, nanoPVD systems are derived from proven R&D thin-film system technology and have been developed through extensive collaboration with leading academic groups. The tools are optimised for ease of use, represent outstanding value for money and are ideal where available space and budgets are key considerations—without compromising on quality of results.



- Benchtop configuration
- Up to 3 × 2" magnetron sputtering sources
- Up to 3 MFC-controlled process gases
- DC and/or RF power options
- Fully automatic operation via touchscreen HMI
- Up to 4" diameter substrates
- Sample heating option
- Turbomolecular pumping system
- Base pressures <math> < 5 \times 10^{-7}</math> mbar
- Define/save multiple process recipes
- Automatic pressure control option
- Equipped for easy servicing
- Comprehensive safety features
- Cleanroom compatible
- Proven performance



LEFT: Model of magnetron sputtering source as fitted to the nanoPVD-S10A.

CENTRE: nanoPVD-S10A chamber baseplate with three magnetron sputtering sources.

RIGHT: View through optional chamber viewport, showing operating magnetron sputtering source on nanoPVD-S10A.

Visit moorfield.co.uk or call +44(0) 1565 722609

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